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Last Name = FUJIEDA

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Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
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09974539	Not Issued	030	10/09/2001	CONTOUR INSPECTION METHOD AND APPARATUS	FUJIEDA, SHIRO
09445304	Not Issued	071	12/06/1999	IMAGE PROCESSING APPARATUS AND METHOD, MEDIUM STORING PROGRAM FOR IMAGE PROCESSING, AND INSPECTION APPARATUS	FUJIEDA , SHIRO
07988921	Not Issued	164	03/12/1993	APPARATUS AND METHOD FOR DECIDING OR SETTING IDEAL LIGHTING CONDITIONS AND PHOTOGRAPHIC CONDITIONS, ETC., IN IMAGE PROCESSING SYSTEM, OR FOR AIDING IN DECIDING OR SETTING OF THE LIGHTING CONDITIONS	FUJIEDA , SHIRO

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1 Dependence of Si pn junction perimeter leakage on the channel-stop dose and interlayer material

Fujieda, S.; Nobusawa, H.; Hamada, M.; Tanigawa, T.;
Electron Device Letters, IEEE, Volume: 20 Issue: 8, Aug. 1999
Page(s): 418 -420

[\[Abstract\]](#) [\[PDF Full-Text \(56 KB\)\]](#) **IEEE JNL**

2 A new encapsulating method for semiconductor devices using resin

Ota, H.; Fujieda, S.; Okuyama, T.;
Electronic Components and Technology Conference, 1997. Proceedings., 47th
May 1997
Page(s): 54 -59

[\[Abstract\]](#) [\[PDF Full-Text \(596 KB\)\]](#) **IEEE CNF**

3 Non-volatile FCG (ferroelectric-capacitor and transistor-gate connected) memory cell with non-destructive read-out operation

Katoh, Y.; Fujieda, S.; Hayashi, Y.; Kunio, T.;
VLSI Technology, 1996. Digest of Technical Papers. 1996 Symposium on, 11
1996
Page(s): 56 -57

[\[Abstract\]](#) [\[PDF Full-Text \(164 KB\)\]](#) **IEEE CNF**

4 A new encapsulating method for semiconductor devices using resin

Ota, H.; Fujieda, S.; Okuyama, T.; Yoshizumi, A.;
Electronic Manufacturing Technology Symposium, 1995, Proceedings of 1995
International, 18th IEEE/CPMT International, 4-6 Dec. 1995
Page(s): 369 -372

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